

### AMENDMENTS TO THE CLAIMS

21. (previously amended) A method of manufacturing a light-emitting device, said method comprising:

forming a light-emitting layer comprised of  $\text{In}_x\text{Ga}_{1-x}\text{N}$  on a sapphire substrate,  
wherein the light-emitting layer has an indium mole fraction  $X$  and emits light of wavelength (nm) =  $1239.8/E_g$  (eV), such that the emitted light has an energy level  $E_g < 3.4 * (1-X) + 1.95 * X - 1.0 * X * (1-X)$ , said light-emitting layer being devoid of an intentional impurity.

22. (previously added) A method according to claim 21, wherein the emitted light has an energy level  $E_g$  approximately calculated in accordance with the following:  $E_g = 3.4 * (1-X) + 1.95 * X - 4.26 * X * (1-X)$ .

23. (currently amended) A method according to claim 22, wherein the indium mole fraction  $X$  is set from about 0.13 to about 0.18 ~~and the light-emitting layer emits light having a peak wavelength ranging from 460 nm to 480 nm.~~

24. (currently amended) A method according to claim 22, wherein ~~the indium mole fraction  $X$  is set from about 0.13 to about 0.18 and~~ the light-emitting layer emits blue light.

25. (currently amended) A method according to claim 22, wherein the indium mole fraction  $X$  ranges from about 0.20 to about 0.23 ~~and the light-emitting layer emits light having a peak wavelength ranging from 510 nm to 530 nm.~~

26. (currently amended) A method according to claim 22, wherein the indium mole fraction  $X$  is set from about 0.19 to about 0.26 ~~and the light-emitting layer emits green light.~~

27. (currently amended) A method according to claim 21, said method further comprising:  
disposing a buffer layer comprising  $\text{AlN}$  on the sapphire substrate;  
~~interposing a first clad layer comprising n-GaN between the buffer layer and the light-~~

~~emitting layer, and~~

~~forming a second clad layer comprising p-GaN doped with magnesium over the light-emitting layer.~~

28. (currently amended) A method according to claim 27, said method further comprising: disposing a transparent electrode ~~comprising gold on the second clad layer and disposing an electrode pad on the first clad layer.~~

29. (previously amended) A method according to claim 27, said method further comprising:

interposing a layer comprising  $\text{Al}_x\text{In}_y\text{Ga}_{1-x-y}$  (including  $X=0$ ,  $Y=0$ ,  $X=Y=0$ ) between the light emitting layer and the second clad layer,

wherein said interposed layer has a wide band gap and is doped with an acceptor.

30. (previously added) A method according to claim 29, wherein the acceptor is a group IIA element.

31. (currently amended)) A method according to claim 29, wherein the ~~acceptor is~~ acceptor comprises magnesium.

32. (previously amended) A method according to claim 27, said method further comprising:

growing the layers as crystals by a metal organic vapor phase epitaxial growth method with nitrogen, ammonia and alkyl compound gases containing a group III element.

33. (New) A method of manufacturing a light-emitting device, said method comprising: forming a light-emitting layer comprised of  $\text{In}_x\text{Ga}_{1-x}\text{N}$  on a sapphire substrate,

wherein the light-emitting layer has an indium mole fraction  $X$ , such that the emitted light has an energy level  $E_g < 3.4 * (1-X) + 1.95 * X - 1.0 * X * (1-X)$ , said light-emitting layer being devoid of an intentional impurity.

34. (New) A method according to claim 23, wherein the light emitting layer emits light having a peak wavelength ranging from 460 nm to 480 nm.
35. (New) A method according to claim 25, wherein the light-emitting layer emits light having a peak wavelength ranging from 510 nm to 530 nm.
36. (New) A method according to claim 26, wherein the light-emitting layer emits green light.
37. (New) A method according to claim 21, said method further comprising interposing a first clad layer comprising n-GaN between the buffer layer and the light-emitting layer.
38. (New) A method according to claim 21, said method further comprising forming a second clad layer comprising p-GaN doped with magnesium over the light-emitting layer.
39. (New) A method according to claim 28, wherein said transparent electrode comprises gold.
40. (New) A method according to claim 27, further comprising forming a second clad layer comprising p-GaN doped with magnesium over the light-emitting layer.